

**Amendments to the Specification:**

Please amend to paragraph on page 19, lines 19-26 [¶ 0098 in the published application] to read as follows:

The o-quinone diazide compound in the positive type photosensitive composition comprising an o-quinone diazide compound is a composition comprising at least one o-quinone diazide group, and it is preferably one which has increased solubility in an alkali aqueous solution as a result of active rays. Many compounds having a variety of structures are known as such compounds, for example, those disclosed in J. Kosar, "Light Sensitive Systems" (John Wiley & Sons, Inc., published in 1965), pp. 336-352. As an o-quinone diazide compound, in particular, sulphone esters of o-quinone diazides or ~~o-naphthoquinone~~ o-naphthoquinone diazides and a variety of hydroxyl compounds are suitable.

Please amend to paragraph on page 20, lines 1-12 [¶ 0099 in the published application] to read as follows:

In the (1) positive type photosensitive composition comprising an o-quinone diazide compound, it is possible to use as a binder resin a resin which is insoluble in water, but soluble in alkali aqueous solutions (below referred to as an alkali soluble resin), and this can improve the developing characteristics, the durability, solvent resistance, chemical resistance and the like. As the alkali soluble resin, for example, a novolak type resin or a resol type resin such as a phenol-formaldehyde resin, a cresol-formaldehyde resin, a phenol-cresol-formaldehyde cocondensed resin, or an acrylic type resin comprising one or more monomers comprising an acidic group, such as polyhydroxystyrene, polyhalogenated hydroxystyrene, N-(4-hydroxyphenyl) methacrylic amide, hydroquinone monomethacrylate, N-(sulfamoylphenyl) methacrylic amide, N-phenyl sulfonyl methacrylic amide, N-phenyl sulphonyl maleimide, acrylic acid, ~~methacrylic~~ methacrylic acid and the like, and the like can be given as examples.